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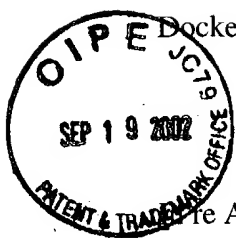
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2121



Docket No.: 5198/Consilium/MBE

PATENT/OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

RECEIVED

SEP 23 2002

Technology Center 2100

Re Application of

Parris C.M. HAWKINS et al.

Serial No. 09/800,980

: Group Art Unit: 2121

Filed: March 8, 2001

: Examiner:

For: DYNAMIC AND EXTENSIBLE TASK GUIDE

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

Serial No. 09/800,980

to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

A handwritten signature in cursive script, appearing to read "Scott M. Alter".

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Date: 9/19/02

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
5198/Consilium/MBESERIAL NO.
09/800,980APPLICANT
Parris C.M. HAWKINS et al.FILING DATE
March 8, 2001GROUP
2121

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	4,698,766	10/06/87	Entwistle et al.			05/17/85
	4,967,381	10/30/90	Lane et al.			07/06/89
	5,208,765	05/04/93	Turnbull			07/20/90
	5,226,118	07/06/93	Baker et al.			01/29/91
	5,231,585	07/27/93	Kobayashi et al.			06/20/90
	5,420,796	05/30/95	Weling et al.			12/23/93
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	5,525,808	06/11/96	Irie et al.			12/20/94
	5,586,039	12/17/96	Hirsch et al.			02/27/95
	5,603,707	02/18/97	Trombetta et al.			11/28/95
	5,664,987	09/09/97	Renteln			09/04/96
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	5,828,778	10/27/98	Hagi et al.			06/12/96
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	61-171147	08/01/86	Japan				X
	6-184434	07/05/94	Japan				X
	0 621 522 A2	10/26/94	Europe			X	
	8-50161	02/20/96	Japan				X
	8-304023	11/22/96	Japan				X

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	February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." <i>IBM Technical Disclosure Bulletin</i> , pp. 4855-4859.
	October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." <i>IBM Technical Disclosure Bulletin</i> , pp. 2857-2860.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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	5,859,964	01/12/99	Wang et al.			10/25/96
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	6,078,845	06/20/00	Friedman			11/25/96
	6,112,130	08/29/00	Fukuda et al.			10/01/97
	6,148,246	11/14/00	Kawazome			06/10/98

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
	11-126816	05/11/99	Japan				X

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	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.
	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp
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	6,175,777	01/16/01	Kim			01/16/98
	6,178,390	01/23/01	Jun			09/08/98
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	6,240,330	05/29/01	Kurtzberg et al.			05/28/97

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	11-135601	05/21/99	Japan				X
	WO 00/05759	02/03/00	WO			X	
	WO 00/35063	06/15/00	WO			X	

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	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer Fabs." Semiconductor FABTECH. www.semiconductorfabtech.com/industry.news/9907/20.07.shtml
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	Johnson, Bob. June 10, 2002. "Advanced Process Control Key to Moore's Law." Gartner, Inc.
	July 9, 2002. International Search Report prepared by the European Patent Office for PCT/US01/24910.
	July 29, 2002. International Search Report prepared by the European Patent Office for PCT/US01/27407.
	Sonderman, Thomas. 2002. "APC as a Competitive Manufacturing Technology: AMD's Vision for 300mm." AEC/APC.
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	6,240,331	05/29/01	Yun			08/18/98
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	6,252,412	06/26/01	Talbot et al.			01/08/99
	6,263,255	07/17/01	Tan et al.			05/18/98
	6,292,708	09/18/01	Allen et al.			06/11/98
	6,298,274	10/02/01	Inoue			09/01/99
	6,303,395	10/16/01	Nulman			06/01/99
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						Yes	No
	WO 00/79355 A1	12/28/00	WO			X	
	2001-76982	03/23/01	Japan				X
	WO 01/33501 A1	05/10/01	WO			X	

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